Electronic Supplementary Information for

Al-doping to Synchronously Improve Conduction Band and Electron Lifetime for SnO₂ Photoanode to Enhance Dye-Sensitized Solar Cells Performances

Yandong Duan,^{†ab} Jiaxin Zheng,^{†a} Nianqing Fu,^{bc} Yanyan Fang,^b Tongchao Liu,^a Qian Zhang,^d Xiaowen Zhou,^b Yuan Lin,^{*ab} and Feng Pan^{*a}

^a School of Advanced Materials, Peking University, Peking University Shenzhen Graduate School, Shenzhen 518055, China. E-mail: linyuan@iccas.ac.cn; panfeng@pkusz.edu.cn; Tel: 86-0755-26033200.

^b Beijing National Laboratory for Molecular Sciences, Key Laboratory of Photochemistry, Institute of Chemistry, Chinese Academy of Sciences, Beijing 100190, China.

^c Department of Applied Physics, The Hong Kong Polytechnic University, Hung Hom, Kowloon, Hong Kong, China.

^d State Key Laboratory for Advanced Metals and Materials, School of Materials Science and Engineering, University of Science and Technology Beijing, Beijing 100083, China.

† Y. D. Duan and J. X. Zheng contributed equally to this work.



 $\label{eq:Fig.S1} \textbf{Fig. S1} \ \text{IPCE} \ \text{of the fabricated DSSCs with } SnO_2, \\ Sn_{0.98}Al_{0.02}O_2, \\ \text{and } Sn_{0.98}Al_{0.02}O_2/\text{TiCl}_4 \ \text{as photoanodes}.$



Fig. S2 EIS spectra of the SnO_2 and the Al-doped SnO_2 DSSCs. The inset of EIS plots represents the equivalent circuit for EIS.

DSSCs based on SnO ₂ photoanode						
Ref.	Morphology or	Diameter	Synthetic method or	Film	η (%) (No surface	η (%)(After surface
	structure		manufacturer	thickness	treatment)	treatment) ^a
S1	SnO ₂	10-30 nm	NanoTek,	6 µm	2.3	
	nanoparticles		SNW15WT%-G02			
S2	SnO_2	3-5 nm	Alfa Aesar	10 µm	1.74	MgO/7.21
	nanoparticles					
S3	SnO_2 nanowire	20-200 nm	reactive vapor	25-30 μm	2.1	TiCl ₄ /4.1
			transport			
S4	SnO_2 hollow	1-2 μm	hydrothermal	10 µm	1.4	TiCl ₄ /5.65
	microspheres					
S5	coral-like SnO ₂	$300 \text{ nm}{\times}2 \mu\text{m}$	wet-chemical		1.04	
S6	SnO_2	15 nm	Alfa Aesar	4 µm	0.76	A1 O /2 7
	nanoparticles				0.70	Al ₂ O ₃ /5.7
S7	meso-SnO ₂	20 nm pores	hard template method	3 µm	1.1	TiCl ₄ /3.8
S 8	SnO_2 nanoflower	1 µm	hydrothermal	8-10 µm	3.00	TiCl ₄ /6.78

S9	SnO ₂ nanoparticles	15 nm	Alfa Aesar	5 µm	1.14	NiO/1.85
S10	SnO ₂ nanoparticles	15 nm	Alfa Aesar		1.7	CaCO ₃ /5.4
S 11	nanoporous SnO ₂	4 nm/>100 nm	Alfa Aesar /Aldrich	1-5µm	2.27	
S12	SnO ₂ nanocrystals	100 nm	microwave solvothermal	10-12µm	3.16	
	SnO_2					
S13	nanoarborous structure		electrodeposition	15µm	0.47	
S14	SnO ₂ nanopowder	<100 nm	Sigma-Aldrich	8µm	3.65	MgO/6.40
S15	SnO ₂ nanotube	110 nm	electrospinning	13µm	0.99	TiCl ₄ /5.11
S16	SnO ₂ nanowires	75±25 nm	electrospinning	19±2 µm	2.53	
S17	Zn-doped SnO ₂ nano-echinus	1 µm	solvothermal	11µm	4.15	
S18	SnO ₂ nanoparticles	100 nm	hydrothermal		0.85	4.15
S19	SnO ₂ hollow nanospheres	200 nm	hydrothermal		0.86	TiCl ₄ /6.02
S20	SnO2 octahedra	0.5 - 1.8 μm	sonochemical	13.2 µm		TiCl ₄ /6.8
S21	SnO ₂ nanosheet	thickness:4-6 nm	hydrothermal	4.1µm	0.23	TiCl ₄ /1.79
S22	mesoporous SnO ₂ agglomerates	200-600 nm	molten salt method	8 µm	3.05	TiCl ₄ /6.23
S23	N-SnO ₂ mesoporous microspheres	1.2-1.5 μm	one-pot solvothermal		2.3	
S24	Sb-doepd SnO ₂ aerogels		sol-gel	10µm	0.7	ALD TiO ₂ /3.5
S25	SnO ₂ hollow	500 nm-2 μm	hydrothermal	11µm		3.6
S26	SnO ₂ nanofibers	200 nm		8.7 μm		TiCl ₄ /4.63
S27	SnO ₂ nanoparticles	11.2-26.2 nm	microwave hydrothermal	13-15 μm	1.35	
S28	SnO ₂ nanoflower	1µm	hydrothermal		1.05	TiCl ₄ /5.6
Our work	Al-SnO ₂ nanocrystals	11.6-15.9 nm	hydrothermal	8 µm	3.56	TiCl ₄ /6.91
DSSCs based on SnO ₂ /TiO ₂ and SnO ₂ /ZnO composites						
S26	SnO ₂ /TiO ₂ composite (1:1)		mechanical blend	7.5 μm		TiCl ₄ /6.17

S29	SnO_2 nanorod@TiO ₂	150 nm×40 nm	flame spray pyrolysis	12 µm	3.95	TiCl ₄ /6.98
S30	SnO ₂ nanoparticles/ZnO nanotetrapods	6-10 nm/40×500 nm	hydrothermal/metal vapor transport- oxidation method	6 µm	6.31	
S31	SnO ₂ nanoparticle-ZnO nanorod	/103-291 nm×7μm	hydrothermal	3 μm +4.4 μm	2.62	
S32	SnO ₂ NRs-TiO ₂	50 nm×5 nm	solution method	150nm+1 0μm	8.61	
S33	SnO_2 hollow spheres-TiO ₂ nanosheets	500 nm	solvothermal reaction	8µm	8.2	

^aSurface treatment method and the corresponding photon-to-electron conversion efficiency.

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